



PRESS RELEASE

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PICOSUN AND NAGOYA UNIVERSITY ANNOUNCE CO-OPERATION IN ATOMIC LAYER DEPOSITION

HELSINKI, Finland and NAGOYA, Japan – October 23, 2007 - Picosun Oy, Finland has entered into a demonstration agreement with Nagoya University, Japan. Professor Zaima's laboratory at Nagoya University has recently purchased a SUNALE™ R-150B ALD reactor manufactured by Picosun. The ALD reactor is equipped with advanced Picosolid™ Booster precursor delivery system, which will make possible the use of a variety of low volatility solid and liquid precursors.

"We are very pleased that Nagoya University has chosen Picosun as its collaboration partner in Atomic Layer Deposition. Prof. Zaima is one of the most highly regarded experts in nanoelectronics and ALD is a great method for producing nanosize structures. We believe that the whole nanoelectronics industry will benefit from our collaboration," says Juhana Kostamo, Managing Director of Picosun Oy.

"Atomic-layer deposition techniques and atomically-controlled nanolaminated films increasingly become important and indispensable in ULSI technologies, so we expect that SUNALE™ R-150B ALD reactor and Picosolid™ Booster system enable us to form novel nano-composite films by using not only conventional liquid sources but also new solid ones.", states Dr. Shigeaki Zaima, Professor of Nagoya University, Japan.

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